



Mr. Ben Eynon

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After graduating from RIT's inaugural Microelectronic Engineering program, Ben Eynon has worked nearly 40 years in the semiconductor industry in the areas of R&D engineering, high volume manufacturing, marketing, and new business development. He has 4 patents and has written, or contributed to over 40 technical articles; and in 2005, he published what is now the photomask industry's handbook entitled, "Photomask Fabrication Technology". He was later assigned by Samsung's Advanced Lithography Division to lead SEMATECH's EUV Resist Test Center and its EUV Mask Blank Development Center. Afterward, he led Samsung-Austin's Lithography Division and then the fab-wide engineering team that developed and installed the world's first 14nm FinFET high volume manufacturing process. He is now at Lam Research helping drive its revolutionary dry resist process and associated infrastructure for advanced EUV patterning.